

# Citations for Ion : Ga

<b>Pub. Year</b>	<b>Authors, Title, Journal Citation and Comments</b>	<b>Citation Numb</b>
<b>1962</b>	Bryde, L. Lassen, N. O. Roy-Poulsen, N. O. <b>'Ranges of Recoil Ions from Alpha-Reactions'</b> <i>Kgl. Danske Videnskab. Selskab Mat. Fys. Medd.</i> , 33, No. 8, 1-28 (1962) Comment : R, dR. (0.6-1.3 MeV) Ga, K -> H2, D2, He, Ar, N, Cu; 3.9 MeV F -> N	<b>1962-Bryd</b>
<b>1964</b>	Lassen, N. O. RoyPoulsen, N. O. Sidenius, G. Vistisen, L. <b>'Stopping of 50 keV Ions in Gases'</b> <i>Kgl. Danske Videnskab. Selskab Mat. Fys. Medd.</i> , 34, No. 5, 1-20 (1964) Comment : R. (50 keV) Na, Ga, Au -> H2, D2, Ne, Ar, He, N2	<b>1964-Lass</b>
<b>1964</b>	Porile, N. T. <b>'Ranges of Low-Energy Gallium Atoms in Copper and Zinc'</b> <i>Phys. Rev. A</i> , 135, 1115-18 (1964) Comment : R. 70-1000 keV Ga -> Cu, Zn	<b>1964-Pori</b>
<b>1964</b>	Sidenius, G. <b>'Measurement of dE/dX in Gases with Low Energy Heavy Particles'</b> <i>M. R. C. McDowell (Ed.) Atomic Collision Processes, North-Holland, Amsterdam, P. 709-16 (1964)</i> Comment : S. (20-50 keV) Cl, Ga, Zr, Sb, Pb, Fe, Ca, Ge, U -> H2	<b>1964-Side</b>
<b>1968</b>	Bowman, W. W. Lanzafame, F. M. Cline, C. K. Yu, Yu-Wen Blann, M. <b>'Recoil Ranges of 0.2 - 5.2 MeV Ions in Vanadium, Nickel, Iron, Zirconium and Gold.'</b> <i>Phys. Rev.</i> , 165, 485-93 (1968) Comment : R, dR. Ion(ZI=12-81, E=0.22-5.2 MeV) -> V, Ni, Zr, Au	<b>1968-Bowm</b>
<b>1968</b>	Bulthuis, K. <b>'Anomalous Penetration of Ga and in Implanted in Silicon'</b> <i>Phys. Letters A</i> , 27, 193-94 (1968) Comment : R, dR. 56 keV In, Ga -> Si (Cryst.)	<b>1968-Bult</b>
<b>1971</b>	Crowder, B. L. <b>'The Influence of the Amorphous Phase on Ion Distributions and Annealing Behavior of Group III and Group V Ions Implanted into Silicon'</b> <i>J. Electrochem. Soc.</i> , 118, 943-52 (1971) Comment : R,dR. (50-300 keV) B, Al Ga, P, As, Sb, Bi -> Si	<b>1971-Crow</b>
<b>1973</b>	Chu, W. K. Crowder, B. L. Mayer, J. W. Ziegler, J. F. <b>'Range Distributions of Implanted Ions in SiO2, Si3N4, and Al2O3'</b> <i>Appl. Phys. Letters</i> , 22, 490-92 (1973) Comment : R, dR. Zn, Ga, As, Se, Cd, Te (140-300 keV) -> SiO2, Si3N4, Al2O3	<b>1973-Chu</b>
<b>1973</b>	Chu, W. K. Crowder, B. L. Mayer, J. W. Ziegler, J. F. <b>'Ranges and Distributions of Ions Implanted into Dielectrics'</b> <i>B.L. Crowder (Ed): Ion Implantation in Semiconductors and Other Materials. Plenum. N. Y. 225-41 (1973)</i> Comment : R.dR. (140-300 keV) Zn, Ga, As, Se, Cd, Te, Zn -> Si, Si3N4, Al2O3	<b>1973-Chu 2</b>

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<b>1973</b>	Gamo, K. Iwaki, M. Masuda, K. Namba, S. Ishihara, S. <b>'Enhanced Diffusion and Lattice Location of Indium and Gallium Implanted in Silicon'</b> <i>Jap. J. Appl. Phys., 12, 735-741 (1973)</i> <i>Comment : R. 45 keV In, Ga -&gt;Si</i>	<b>1973-Gamo</b>
<b>1975</b>	Ambridge, T. Heckingbottom, R. <b>'Effect of Dual Implants into GaAs'</b> <i>Elec. Letters, 11 (1975)</i> <i>Comment : R. 350 keV Se, Ga -&gt;GaAs</i>	<b>1975-Ambr</b>
<b>1975</b>	Dearnaley, G. Gard, G. A. Temple, W. Wilkins, M. A. <b>'Depth Distribution of Gallium Ions Implanted into Silicon Crystals'</b> <i>Appl. Phys. Letters, 27, 17-18 (1975).</i> <i>Comment : R, dR. 40 keV 72Ga -&gt; Si (Cryst.)</i>	<b>1975-Dear</b>
<b>1976</b>	Grant, W. A. Dodds, D. Williams, J. S. Christodoulides, C. E. Baragiola, R. A. <b>'Heavy Ion Ranges in Silicon and Aluminum'</b> <i>Ion Implantation in Semiconductors, Ed. by F. Chernow, J. A. Borders, D. K. Brice, 693-703 (1976)</i> <i>Comment : R. 0.01 &lt; Epsilon &lt; 0.8 Cr, Ni, Ga, As, Br, Mo, Cs, La, Nd, Dy, Ta, Pt, Au, Pb -&gt; Si, Al</i>	<b>1976-Gran</b>
<b>1976</b>	Hirvonen, J. K. Hubler, G. K. <b>'Application of a High-Resolution Magnetic Spectrometer to Near-Surface Analysis'</b> <i>Meyer, G. Linker and F. Kappeler (Ed.): Ion Beam Surface Layer Analysis, Plenum, N. Y., P. 457-69 (1976)</i> <i>Comment : R, dR. 2-60 keV 209Bi, 60 keV 69Ga -&gt; Si</i>	<b>1976-Hirv</b>
<b>1978</b>	Furuya, T. Nishi, H. Inada, T. Sakurai, T. <b>'Channeled-Ion Implantation of Group-III and Group-V Ions into Silicon'</b> <i>J. Appl. Phys., 49, 3918-3921 (1978).</i> <i>Comment : R, dR. 100-300 keV B, P, As, Al, Ga -&gt; Si [111], [110], Random</i>	<b>1978-Furu</b>
<b>1978</b>	Shin, B. K. Ehret, J. E. Park, Y. S. Stefiniw, M. <b>'Dual Implantation of C+ and Ga+ Ions into GaAs'</b> <i>J. Appl. Phys., 49, 2988-2990 (1978)</i> <i>Comment : R. 120 keV Ga, 60 keV C -&gt; GaAs</i>	<b>1978-Shin</b>
<b>1979</b>	Santry, D. C. Werner, R. D. Westcott, O. M. <b>'The Range of 120 keV Ions in Solids'</b> <i>IEEE Trans. Nucl. Sci., Ns-26, 1331-1334 (1979)</i> <i>Comment : R, dR. 120 keV Mg, Al, P, S, Cl, K, Ar, Cr, Mn, Cu, Zn, Ga, As, Br, Kr, Rb, Ag, In, Sn, Sb, Te, I, Xe, Cs, Ba, Pr, Au, Hg, Tl, Pb, Bi -&gt; Be, C, Al, Si</i>	<b>1979-Sant</b>
<b>1984</b>	Behar, M. Beirsack, J. P. Fichtner, P. F. P. Fink, D. Leite-Filho, C. V. <b>'Range and Range Straggling of 15-350 keV Ga in Amorphous Silicon'</b> <i>Rad. Effects Letters, 85, 117-122(1984)</i> <i>Comment : R, dR. Ga (15-350 keV) -&gt; Si</i>	<b>1984-Beha</b>

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<i>Pub.</i>	<i>Authors, Title, Journal Citation and Comments</i>	<i>Citation Numb</i>
<b>Year</b>	Ingram, D. C. Baker, J. A. Walsh, D. A. Strathman, E. <b>1987</b> 'Range Distributions of MeV Implants in Silicon - 2' <i>Nucl. Inst. Methods, B21, 460-465 (1987)</i> <i>Comment : R, dR, B, P, Ga (0.4-6.0 MeV) -&gt; Si</i>	<b>1987-Ingr</b>